Murad A Redzheb

List of Publications by Year in descending order

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1307594 1281871 13 108 7 11 citations g-index h-index papers 14 14 14 133 docs citations times ranked citing authors all docs

#	Article	IF	CITATIONS
1	Extrusion bioprinting of hydroxyethylcellulose-based bioink for cervical tumor model. Carbohydrate Polymers, 2021, 260, 117793.	10.2	25
2	Selective dissolution of amorphous and nanocrystalline Zr2Ni. Corrosion Science, 2013, 74, 308-313.	6.6	16
3	Effect of the C-bridge length on the ultraviolet-resistance of oxycarbosilane low-k films. Applied Physics Letters, 2016, 108, .	3.3	11
4	A detailed ellipsometric porosimetry and positron annihilation spectroscopy study of porous organosilicate-glass films with various ratios of methyl terminal and ethylene bridging groups. Microporous and Mesoporous Materials, 2020, 306, 110434.	4.4	11
5	Effect of the C-bridge on UV properties of organosilicate films. Thin Solid Films, 2019, 685, 329-334.	1.8	10
6	Influence of boron on the hydriding of nanocrystalline Mg2Ni. Intermetallics, 2013, 34, 63-68.	3.9	8
7	UV cure of oxycarbosilane low-k films. Microelectronic Engineering, 2016, 156, 103-107.	2.4	8
8	On the mechanical and electrical properties of self-assembly-based organosilicate porous films. Journal of Materials Chemistry C, 2017, 5, 8599-8607.	5.5	7
9	Template-dependent hydrophobicity in mesoporous organosilica films. Microporous and Mesoporous Materials, 2018, 259, 111-115.	4.4	7
10	Tuning the Properties of Periodic Mesoporous Organosilica Films for Lowâ€k Application by Gemini Surfactants. ChemPhysChem, 2018, 19, 2295-2298.	2.1	2
11	Laser anneal of oxycarbosilane low-k film. , 2016, , .		1
12	Periodic Mesoporous Organosilica Films with a Tunable Steadyâ€State Mesophase. ChemPhysChem, 2017, 18, 2846-2849.	2.1	1
13	Enabling bottom-up nanoelectronics fabrication by selective sol–gel dielectric-on-dielectric deposition. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2021, 263-114808	3.5	1